

ABSTRACT

Provided is a vapor deposition unit which is fit for universal uses and which is superior in maintenance property.

A vapor deposition unit (VU) of this invention is provided with: a container box (3) for containing therein a vapor deposition material (Vm); and a heating means (4) for heating the vapor deposition material inside the container box, and which has formed in one plane of the container box a discharge opening (34c) for discharging a sublimated or evaporated vapor deposition material as a result of heating. The vapor deposition unit is further provided, inside a storing chamber (30), with a moving means (5) for moving the vapor deposition unit. Provided that a direction looking toward the opening in the storing chamber is defined as an upper side, the moving means moves the vapor deposition unit disposed in the storing chamber in an up-and-down direction in a posture coinciding with a phase of the discharge opening.